

FIG. 1

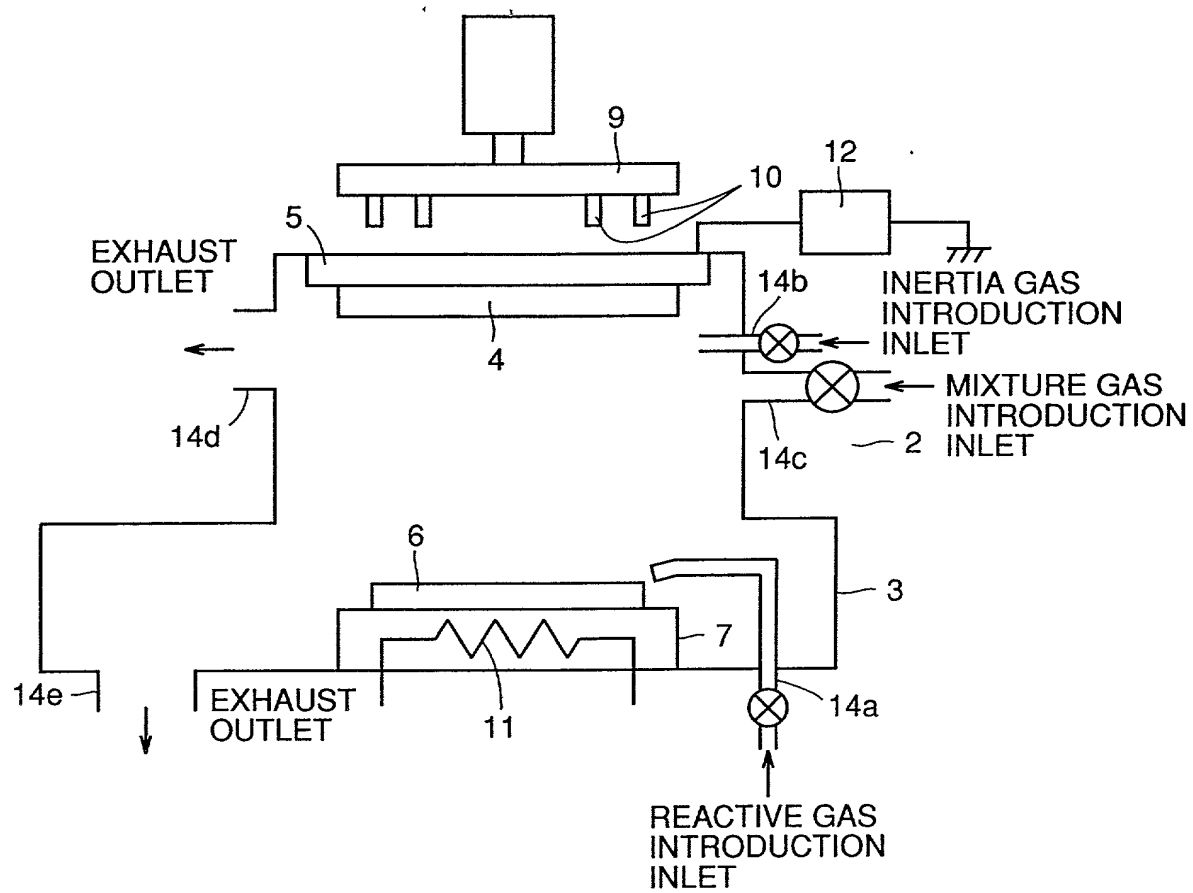
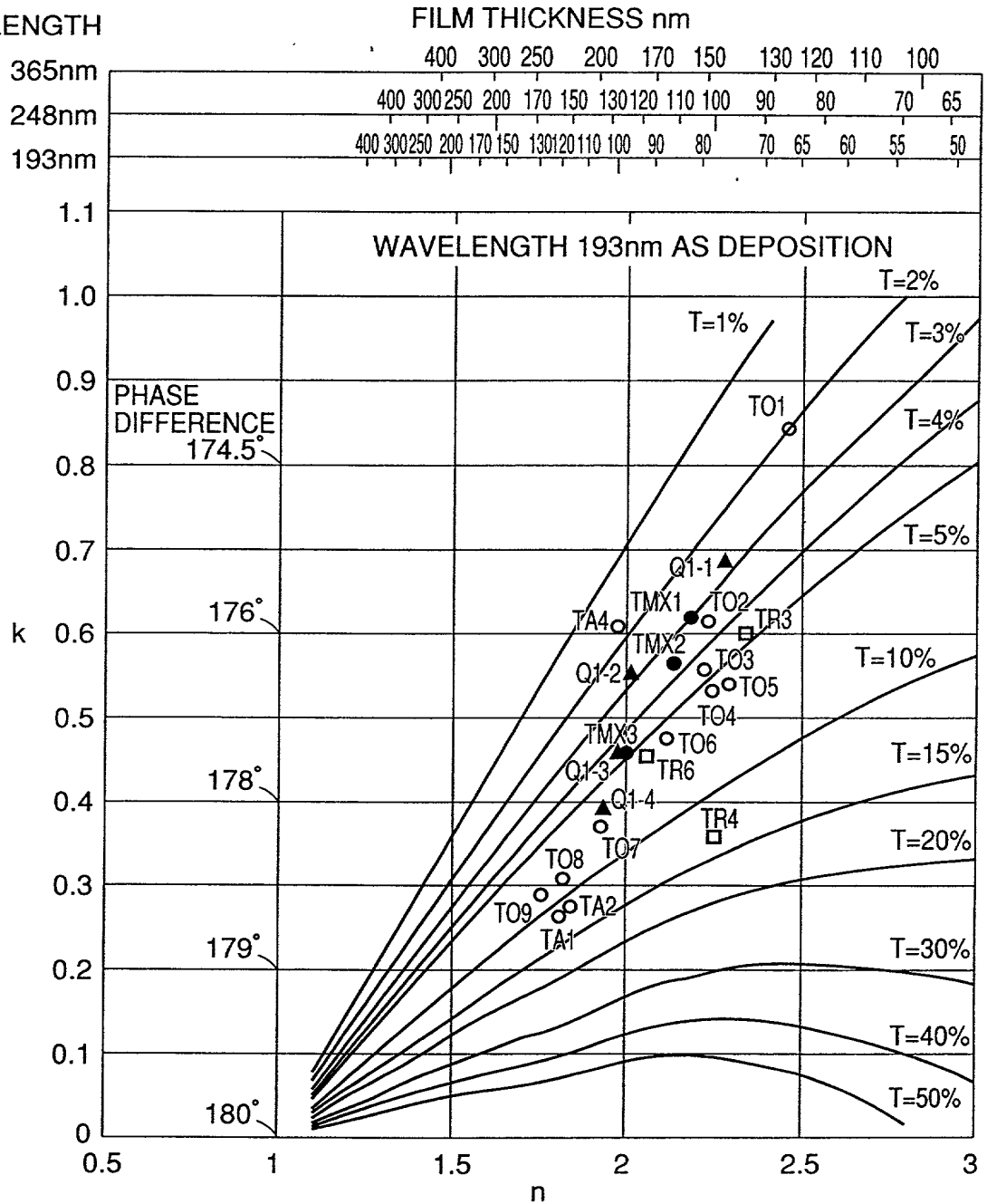


FIG.2

EXPOSURE
LIGHT
WAVELENGTH



EXPOSURE
LIGHT
WAVELENGTH

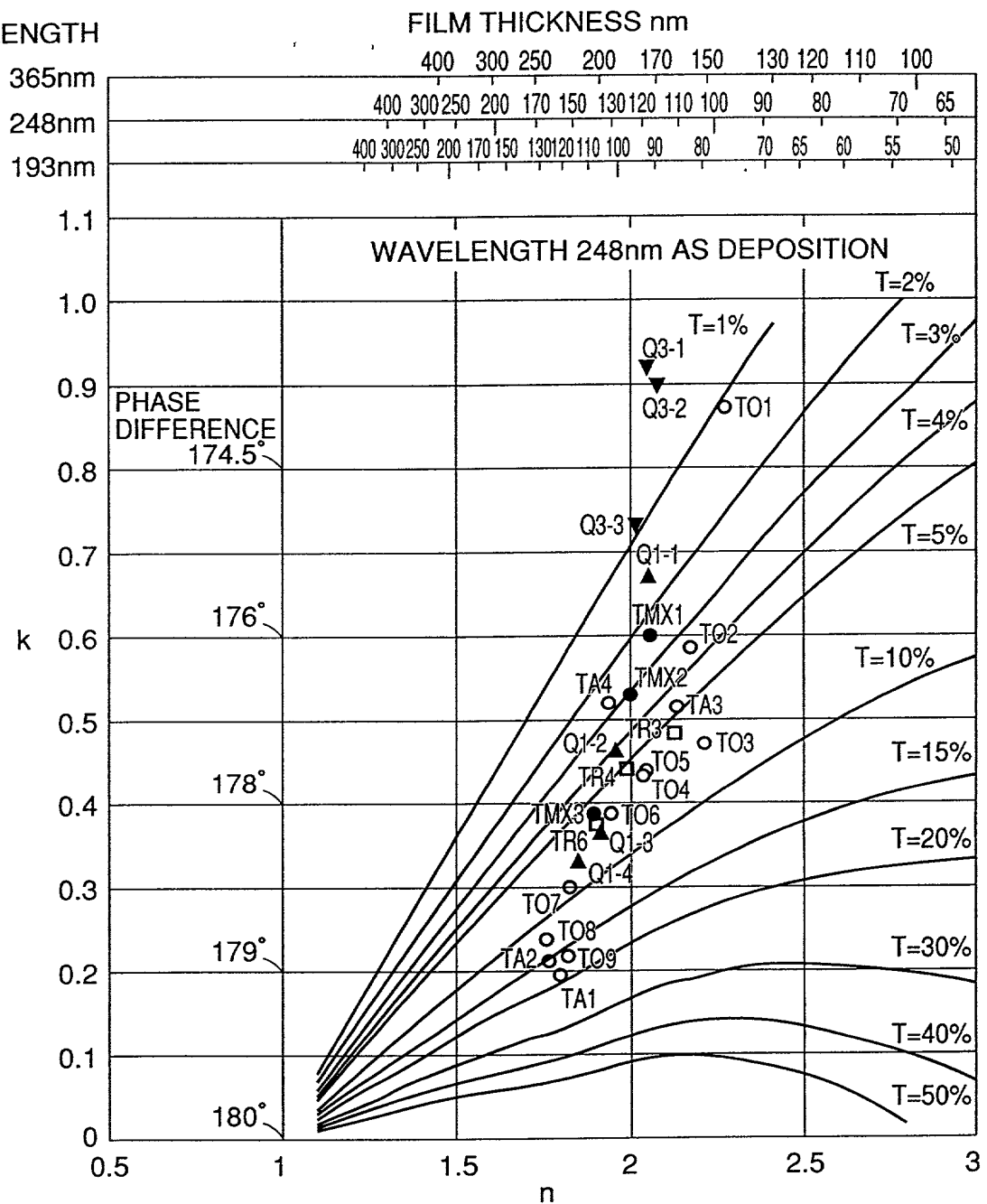


FIG.4

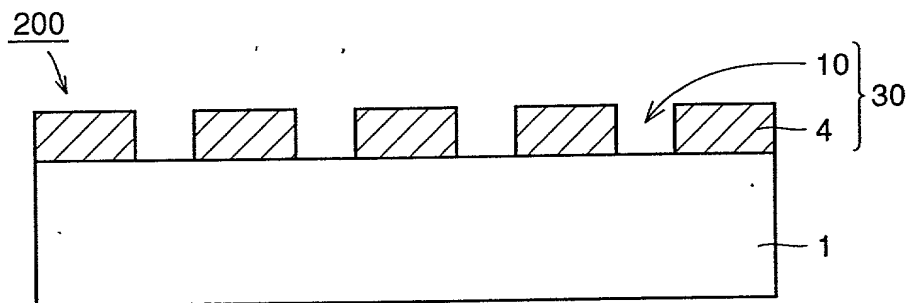


FIG.5A

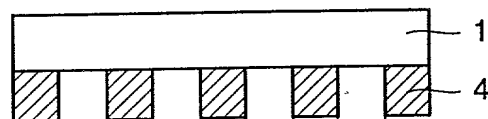


FIG.5B

ELECTRIC FIELD
ON THE MASK

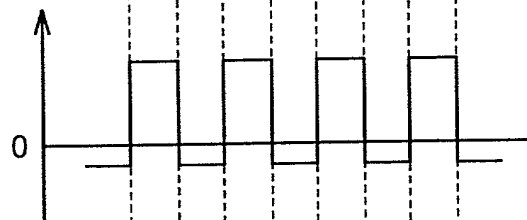


FIG.5C

LIGHT INTENSITY
ON THE WAFER

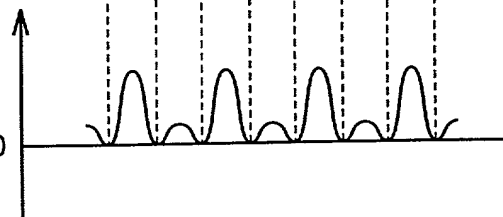


FIG.6

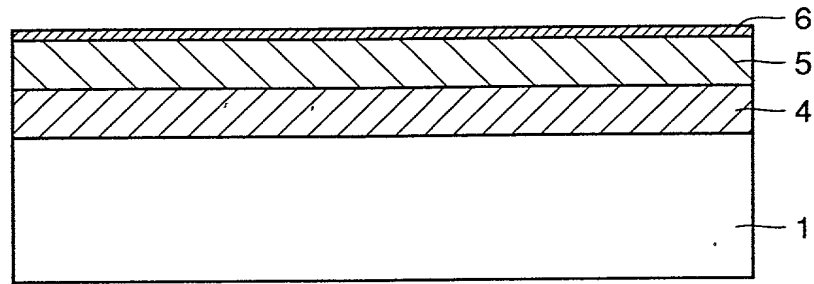


FIG.7

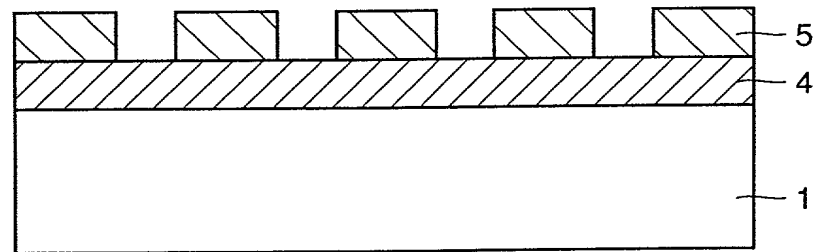


FIG.8

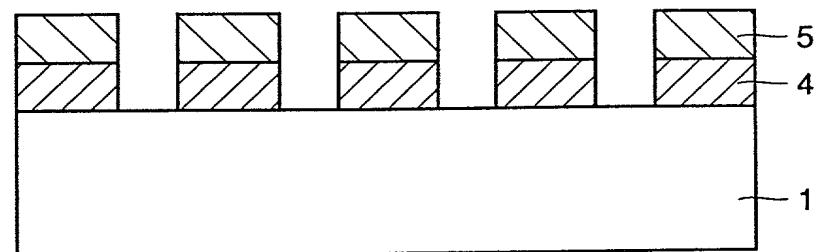


FIG.9

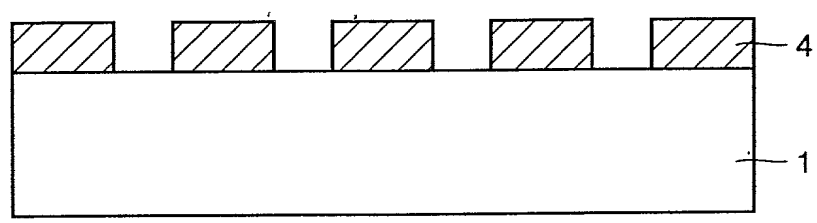


FIG.10

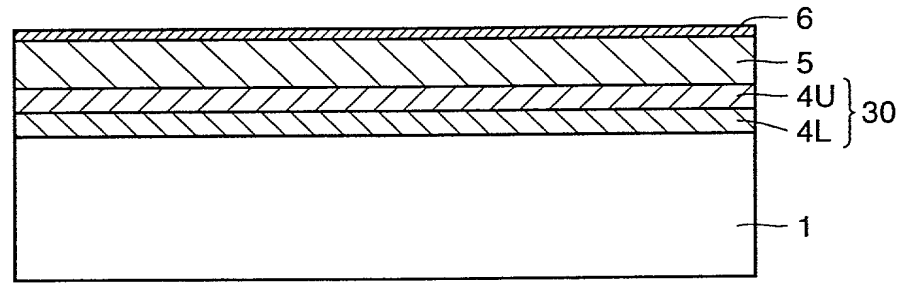


FIG.11

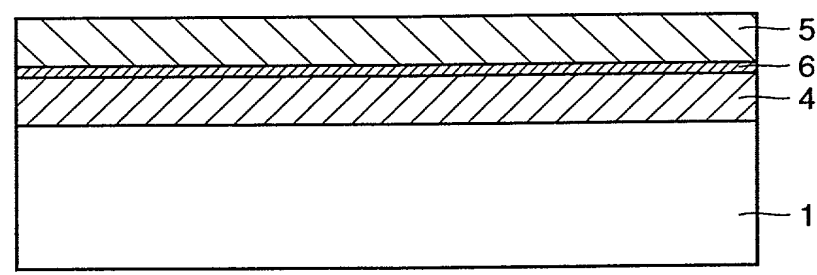


FIG.12

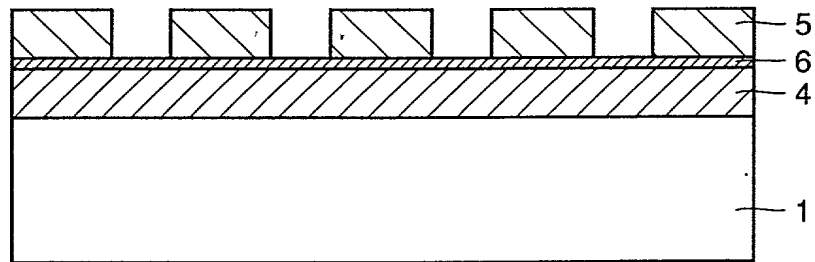


FIG.13

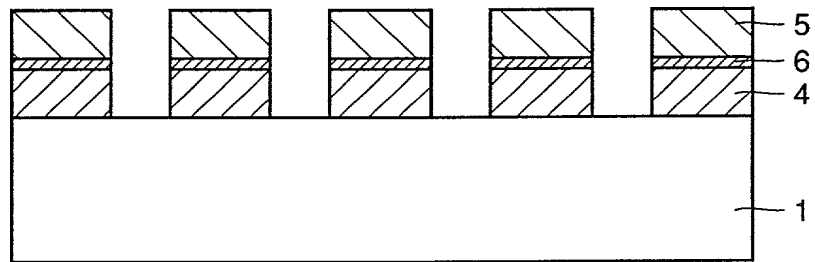


FIG.14

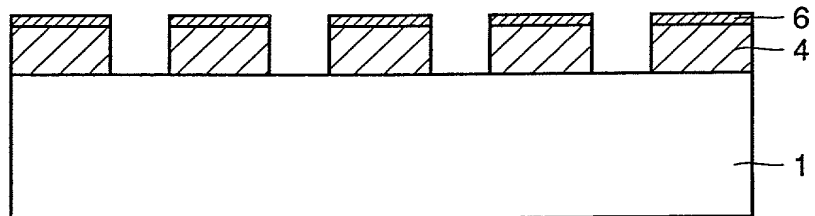


FIG.15

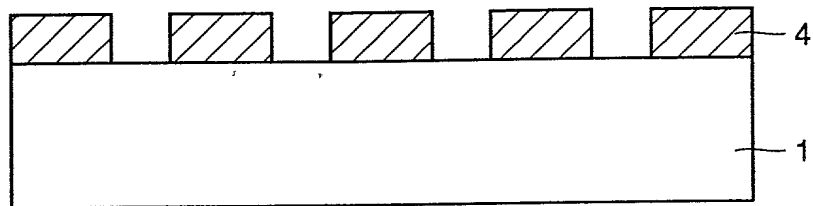


FIG.16A

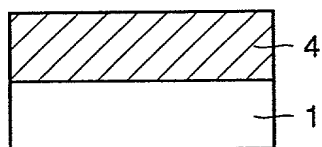


FIG.16B

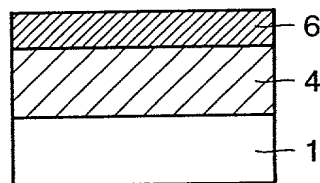


FIG.17A

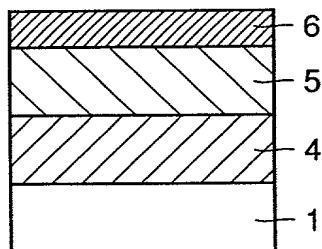


FIG.17B

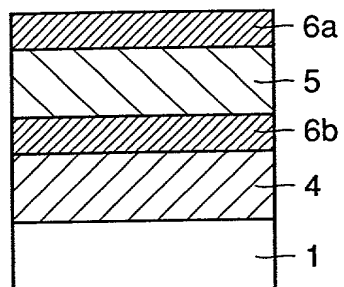


FIG.18

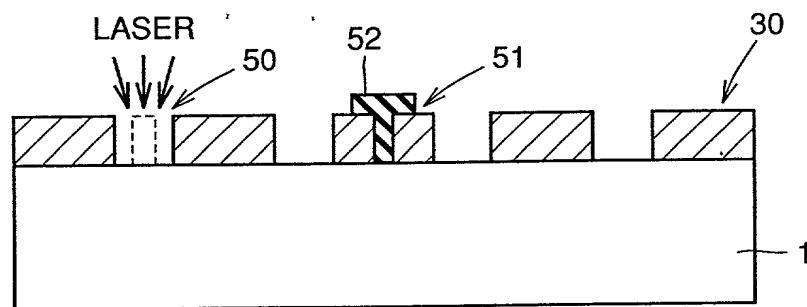


FIG.19

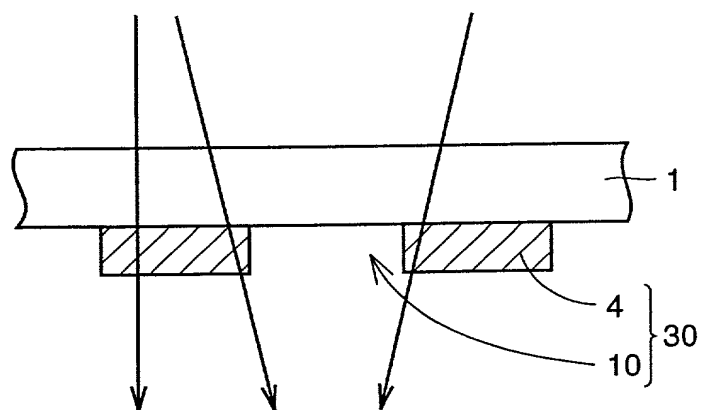


FIG.20

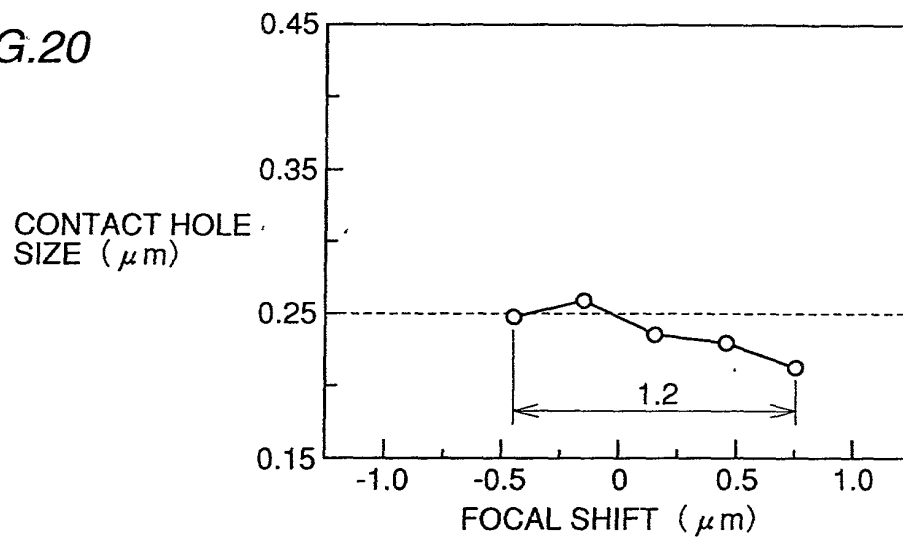


FIG.21

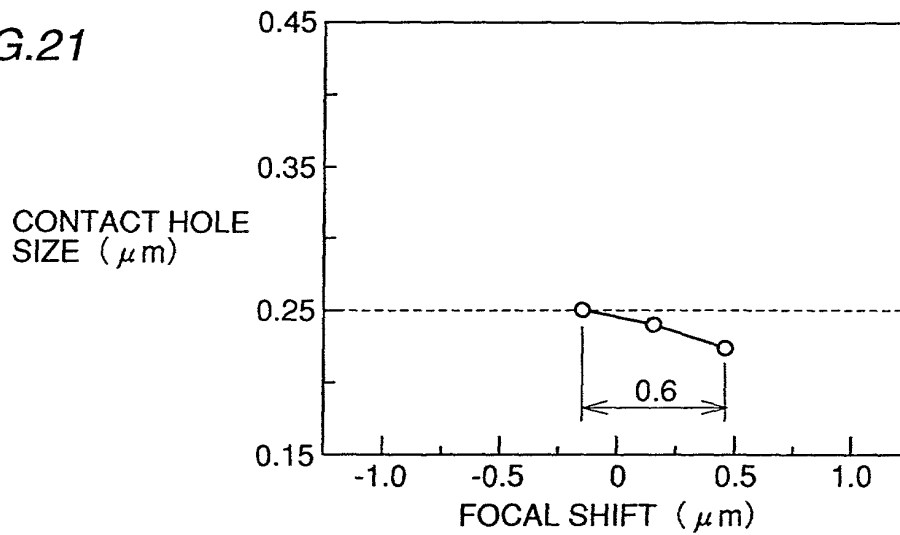


FIG.22

